

# **SIC MANUFACTURING IN THE FOUNDRY MODEL SEPTEMBER 2014**

# Company History



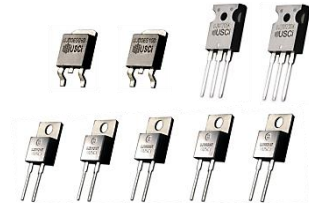
**SiC Research**  
Launched by  
Rutgers University

**Prototypes of SiC**  
Schottky Diodes,  
MOSFETs, JFETs



**New HQ Established**  
Built in-house 4" FAB

**Q1: Production Release xR**  
1200V & 650V JBS Diode Series  
1200V Normally-on JFETs



**Prototypes DC-DC**  
Converters, High  
Frequency Power  
Switch, SiC Modules  
for DOD, DOE

**ACQUIRED BY  
DOLCE MGMT  
TEAM**


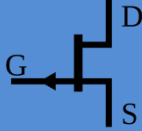

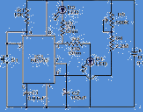
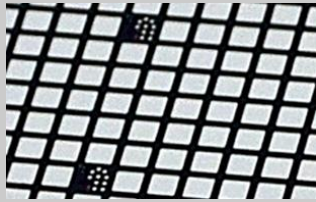


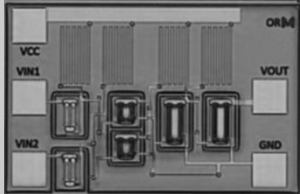


Princeton, NJ  
"Einstein's Alley"

**Fab-Lite model**  
On-Line With  
Foundry Partner To  
Increase Capacity

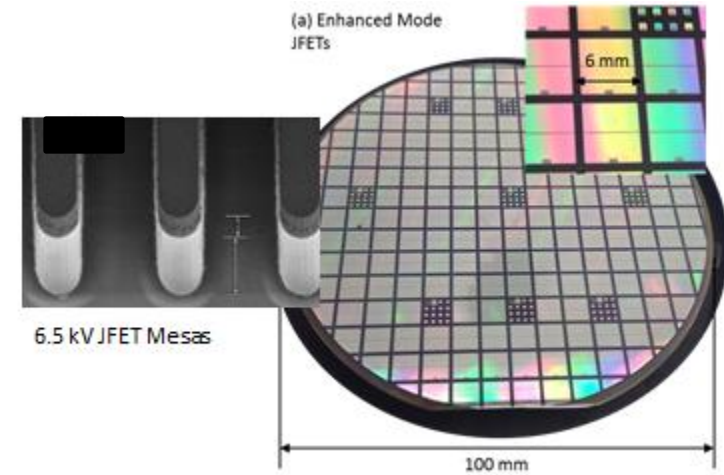
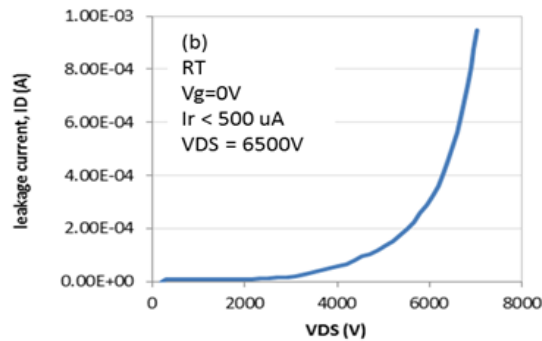
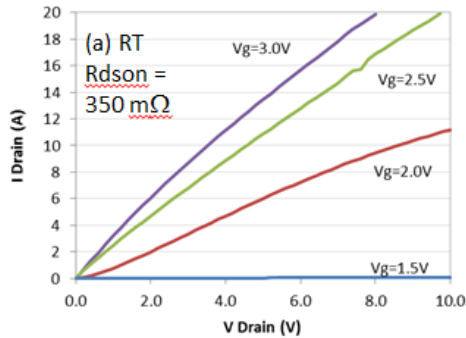
**Q4: Production Release**  
1200V Cascode Series

# SiC Technology Focus Areas

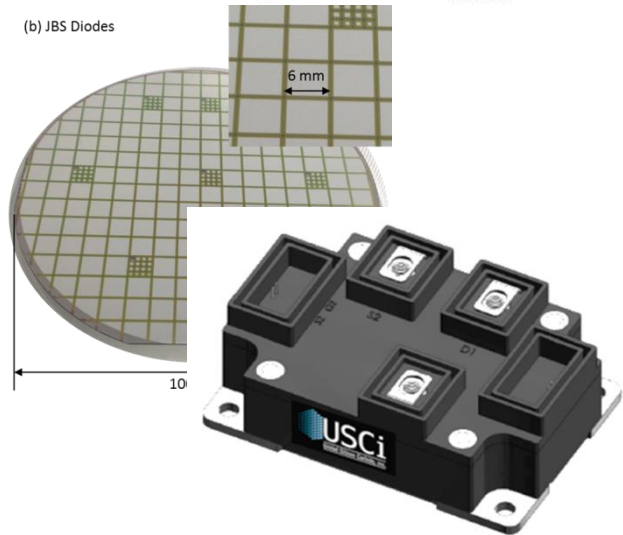
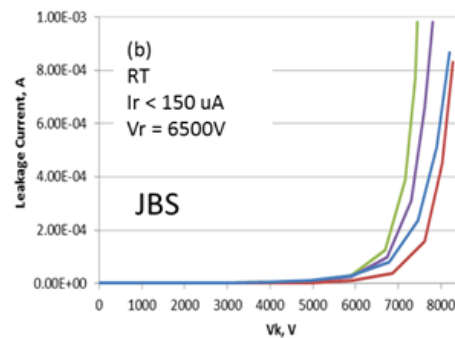
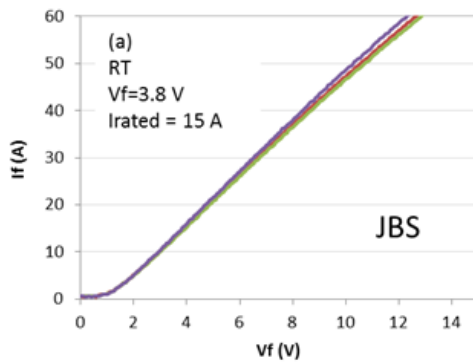
<p><b>JBS</b></p> 	<p><b>JFET</b></p> 	<p><b>MOSFET</b></p> 	<p><b>IC</b></p> 
			
<p><b>650V – 16kV</b></p>	<p><b>650V-6.5kV</b></p>	<p><b>1200V – 10kV</b></p>	<p><b>50V</b></p>
<p>Low <math>V_F</math> Zero <math>Q_{RR}/T_{RR}</math> 175°C package 250°C die</p>	<p>Normally On &amp; Off Ultra low FOM Minimal <math>E_{ON}</math> &amp; <math>E_{OFF}</math> 175°C package 250°C die</p>	<p>Low <math>R_{DS(ON)}</math> Low <math>Q_{GD}</math>, <math>Q_G</math> 150°C</p>	<p>500°C <math>T_{J(MAX)}</math></p>

# USCI 6500V DEVICES PROTOTYPES

## 6.5KV N-off JFETs



## 6.5KV JBS Diodes



# History of the foundry model in power devices

2008-today

Expansion to 12inch limited. New FAB investments small - most suppliers trying to exploit overcapacity at 8inch. Outsourcing older tech to meet demand.

2005-2008

8inch Foundry model applied to FS-IGBTs and Superjunction technologies. Top suppliers still operate in-house FABs.

Late 90s-2000s

8inch Foundry model appears for low voltage MOSFETs – while most incumbents are still at 6inch

1970s-1990s

Power Discretes use custom processes and architectures. Fabs work with previous generation CMOS equipment. Top suppliers own their FABs (5in-6in)

# The foundry model in SiC

## PROS

- Silicon foundries bring a lot of established baseline expertise and manufacturing discipline
- High uniformity and high throughput processing equipment
- Foundries of sufficient scale with a solid (non-SiC) base business can offer reduced process costs
- By aggregating the SiC business from multiple companies, they can generate more economies of scale
- Capital efficient for ramping volume production

## CONS

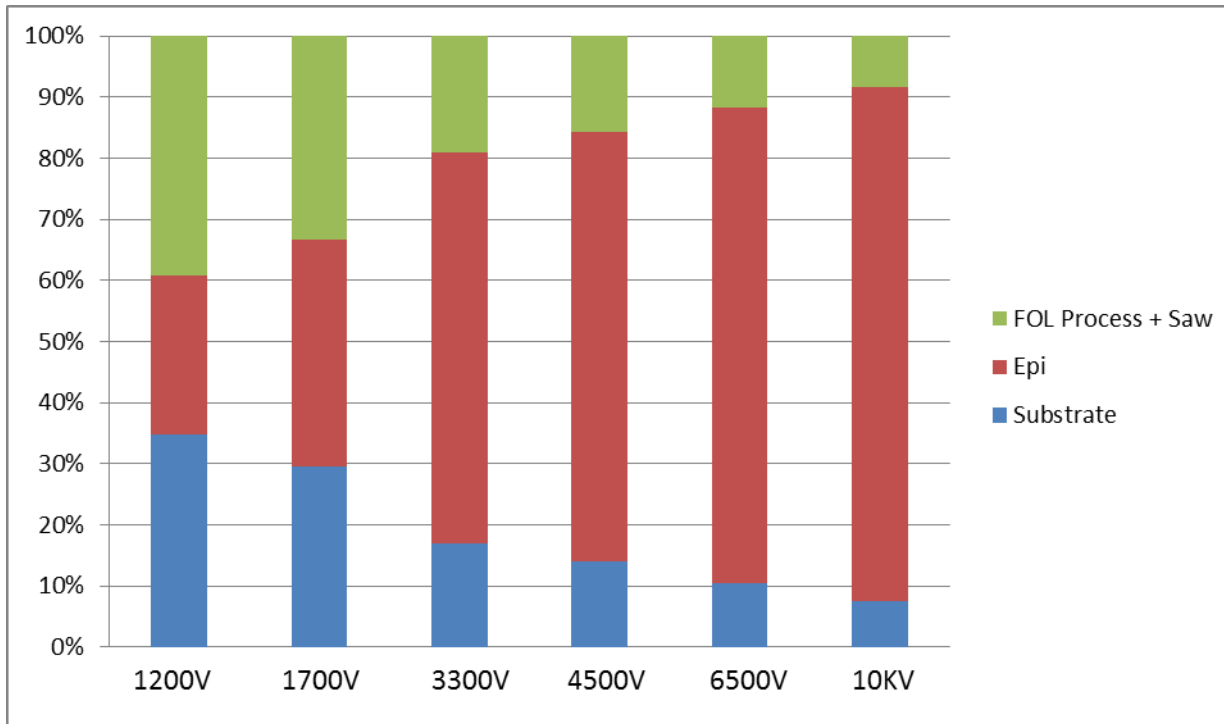
- Most foundries need consigned equipment to enable a SiC process
- Concerns about IP protection – exclusivity can defeat the cost benefit from volume aggregation.
- Speed of technology development
- Volume projections in the near term 2-3 years are still too low to justify large investments
- Capacity and engineering resource allocation

# Economics of 6inch foundry process costs

Fab size	Fab Outs/mo	Monthly Running costs	Cost/Wafer at 80% utilization
Small	1000	\$1,000,000	\$1,250
Small	10000	\$2,000,000	\$250
Medium	30000	\$3,000,000	\$125
Large	60000	\$4,000,000	\$83

- Total fab volume and utilization drive costs – must find SiC volume drivers, or share the factory with other volume contributors
- High cost tools with limited throughput drive up costs – SiC has several such bottlenecks in epi, implant, backgrind, saw. These are being rapidly improved.

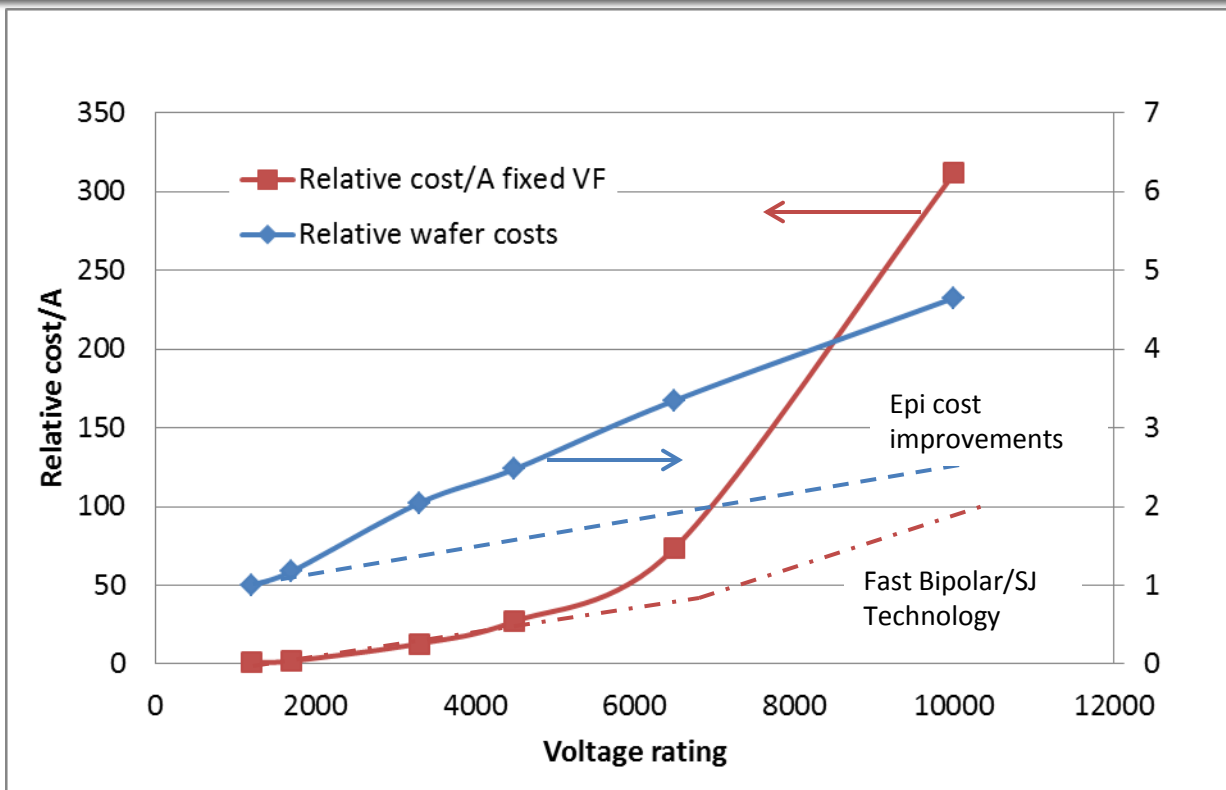
# High voltage devices and their cost drivers



- Epi cost dominates present day SiC high voltage costs – area needing rapid improvement in throughput without worsening quality
- For pure unipolar devices (JBS Schottky, MOSFET, JFET), several large chips needed for meet the current requirements.



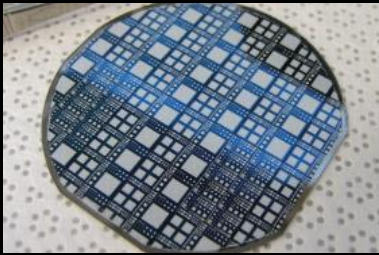
# Transistor/diode costs



- Unipolar device costs always increase with voltage rating since  $R_{dsA} \propto BV^{2.5}$
- Flattening the epi cost curve can drive down costs substantially
- Long term: need to get bipolar options to flatten the  $R_{dsA} - BV$  relationship

# Summary

- The foundry model brings down wafer FAB costs, allow volume ramp with targeted capital expenditures, and brings Si high volume manufacturing capability to SiC.
- This translates both to stable high yields, as well as the ability to quickly deliver large volumes.
- Technological progress is needed and ongoing to drive down epitaxy costs for >3300V devices.
- Insertion of medium voltage diodes into IGBT modules can bring benefits in efficiency and improved operating lifetimes from lower operating temperatures.
- HV transistor solutions have a lot of promise, and initial products must be seeded to allow engineers to work on all the system issues with fast switching at 5-10KV.



Thank You!

USCi Welcomes Your Questions

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